Friedrich-Alexander-Universität **Technische Fakultät**

21th-23th May,2024, Erlangen, Germany

 \bigcirc

stract



Nanoimprint Lithography-Dependent Vertical Composition Gradient in Pseudo-Planar Heterojunction Organic Solar Cells Combined with Sequential Deposition Houdong Mao¹, Lifu Zhang^{2*}, Yiwang Chen^{1,2,3*} ¹College of Chemistry and Chemical Engineering/Institute of Polymers and Energy Chemistry (IPEC) Nanchang University 999 Xuefu Avenue, Nanchang 330031, China ²National Engineering Research Center for Carbohydrate Synthesis/ Key Lab of Fluorine and Silicon for Energy Materials and Chemistry of Ministry of Education Jiangxi Normal University 99 Ziyang Avenue, Nanchang 330022, China ³College of Chemistry and Chemical Engineering, Gannan Normal University, Ganzhou 341000, China

 \triangleright **Background:** Although suitable vertical phase separation morphology in organic solar cells (OSCs) can be obtained by the donor/acceptor sequential deposition (SD) method, the lack of precisely adjusting vertical composition gradient and molecular crystallinity is a key limitation.

- Idea: Nanoimprint lithography (NIL) combined with SD dual-functionalized regulation strategy is first used to fabricate high-performance pseudoplanar heterojunction (PPHJ) OSCs, which is conducive to constructing vertical bi-continuous donor/acceptor network to provide sufficient charge separation interface area and orderly charge transport channels.
- **Conclusion:** PM6 donor with regular periodic nanograting structure and improved crystallinity is formed via NIL, effectively avoiding the erosion problem ascribed from the subsequent depositing of the Y6 acceptor. And the best-imprinted device enables a power conversion efficiency as high as 17.36%, which is higher than the control SD-based device (15.46%).





Fig 2. Optical microscope images, SEM images, AFM images and phase diagrams > Nanograting can be gained and the generated larger contact area can facilitate exciton dissociation.

National Natural Science Foundation of China (NSFC) (51833004, U20A20128, M-0327, 52063019, 51973088, 51903189).

H. Mao, L. Zhang, L. Wen, L. Huang, L Tan,* and Y Chen*, Adv. Funct. Mater. 2022, 33, 2209152. H. Mao, L. Wen, L. Zhang,* J. Zhang, Z. Qin, L. Tan,* and Y. Chen*, Adv. Mater. 2023, 36, 2308159.